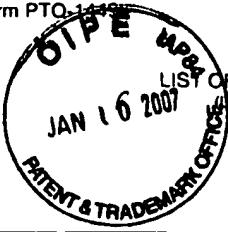


Form PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF ART CITED BY APPLICANT <small>(use several sheets if necessary)</small>					ATTY. DOCKET NO. MI22-2310	SERIAL NO. 10/643,680	
					APPLICANT: Kraus et al.		
					FILING DATE August 18, 2003	GROUP 1762	
U.S. PATENT DOCUMENTS							
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
BT	AA	6,203,613	03/01	Gates et al.			
BT	AB	10/196,814	07/02	Kyung-In			
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
	AJ						Yes No
	AK						
	AL						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
BT	AM		Park et al., "Plasma-Enhanced Atomic Layer Deposition of Tantalum Nitrides Using Hydrogen Radicals as a Reducing Agent", Electrochemical and Solid-State Letters, 4 (4) C17-C19, The Electrochemical Society, Inc. (2001).				
	AN						
	AO						
EXAMINER <i>/Brian Talbot/</i>		DATE CONSIDERED 02/06/2007					
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							

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